

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Hiroe KAWAMURA**

Group Art Unit: **2891**

Application Number: **10/782,770**

Examiner: **Igwe U. Anya**

Filed: **February 23, 2004**

Confirmation Number: **7652**

For: **SEMICONDUCTOR DEVICE AND MANUFACTURING METHOD  
THEREOF**



Attorney Docket Number: **042138**

Customer Number: **38834**

**INFORMATION DISCLOSURE STATEMENT**  
**UNDER 37 C.F.R. §1.97(b)**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

August 15, 2006

Sir:

In compliance with 37 C.F.R. §1.56, Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached PTO/SB/08. This paper is being filed within the time periods set forth in 37 C.F.R. §1.97(b). A copy of each non-U.S. document is enclosed herewith.

JP 2004-152965 provides a manufacturing method of a semiconductor device which is capable of reducing micro roughness on a surface of a silicon substrate. In contrast, the present invention provides a manufacturing method of a semiconductor device which is capable of reducing micro roughness on a surface of a silicon substrate and further which capable of enhancing mobility of carries by specifying the moving direction of the carriers in the semiconductor device.

If there are any fees due in connection with the filing of this paper, please charge Deposit Account No. 50-2866.

Respectfully submitted,

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Enclosures: PTO/SB/08  
1document

**Combined Form PTO/SB/08A&B**

## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

*(use as many sheets as necessary)*

*Complete if Known*

Application Number	10/782,770
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First Named Inventor	Hiroe KAWAMURA
Art Unit	2891
Examiner Name	Igwe U. Anya
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## U.S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

## NON PATENT LITERATURE DOCUMENTS

[illegible]

Examiner Signature		Date Considered	
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kind Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov), MPEP 901.04 or in the comment box of this document. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST. 3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to indicate here if English language Translation is attached.